

# **SP1.5.6: High-Efficiency Power Electronics Switching for Alternative Energy Applications**



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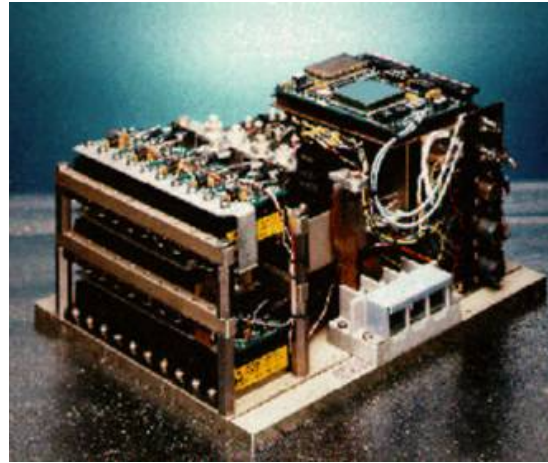
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# Need More Efficient Semiconductor Power Switch



**Silicon Power Switch**

50,000 cm<sup>3</sup>  
18 kg

Shenai's Figure of Merit -

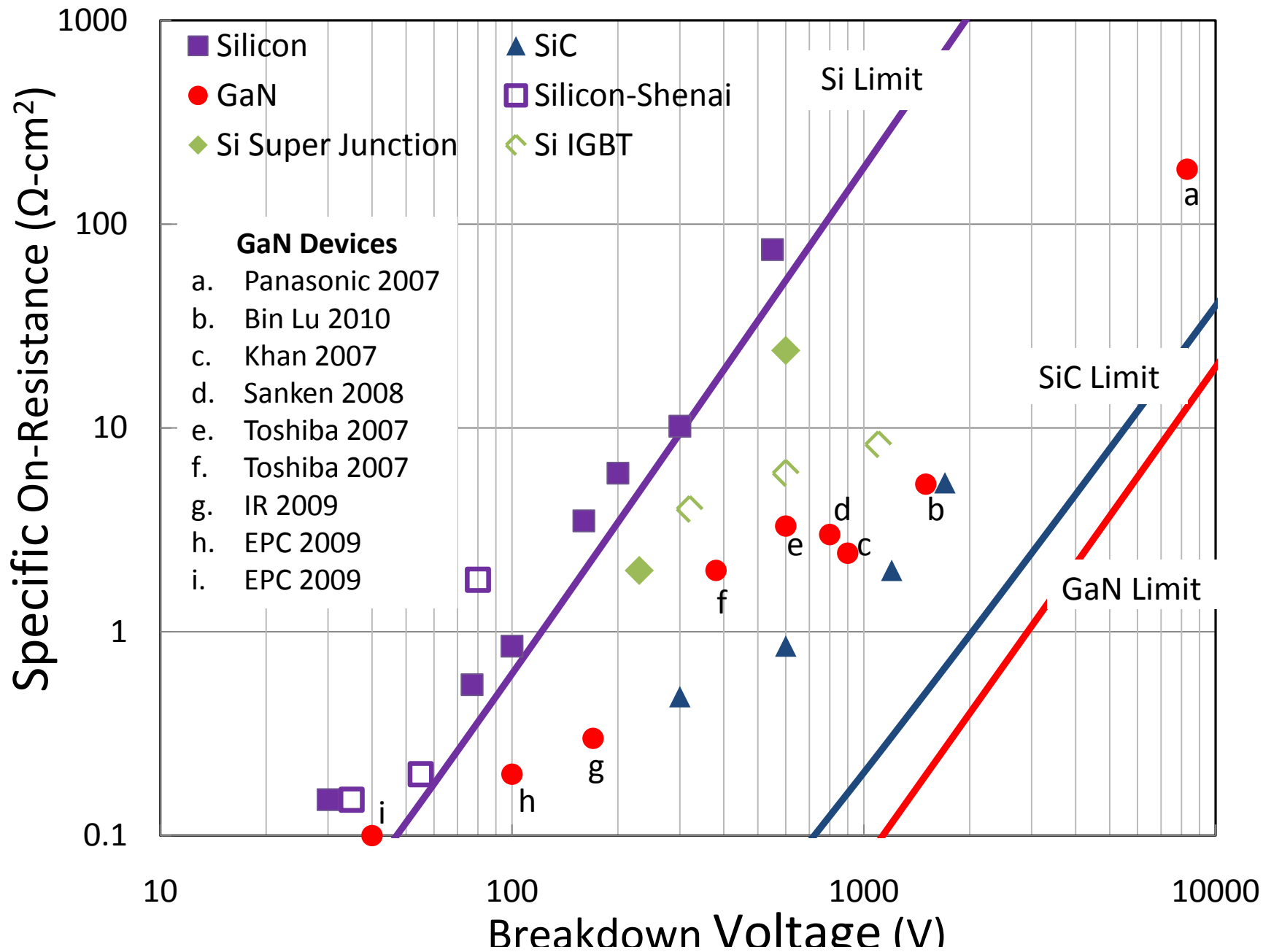
$$Q_{F2} = \lambda \sigma_A E_M$$

2400x improvement

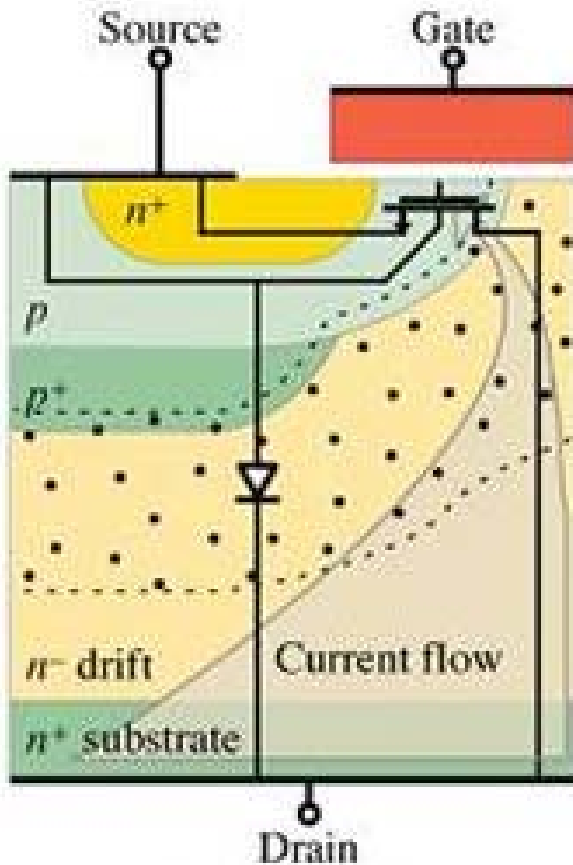


**SiC or GaN Power Switch**

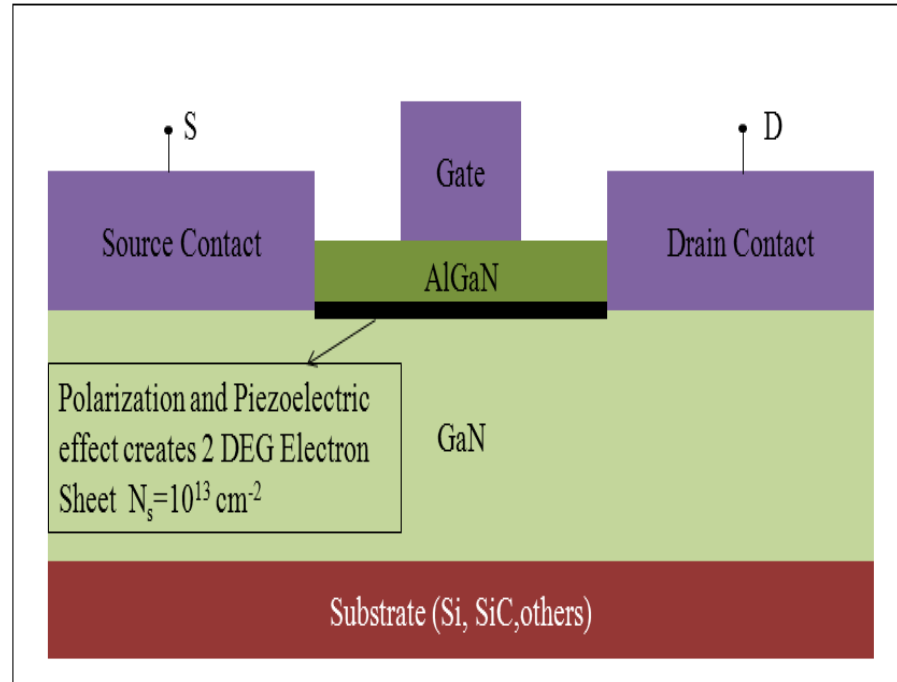
4,500 cm<sup>3</sup>  
0.2 kg



# Vertical vs. Lateral Devices



**Silicon Vertical  
DMOSFET**



**GaN Lateral  
HEMT**

$$R_{sp} = \frac{4V_B^2}{\epsilon_s \mu E_C^3}$$

# Point-of-Load (POL) Converter Application in Cell Phones



2

10 – 20%

External LDO, SMPS

Backlight  
Driver  
High Voltage  
Low Current

3

Hybrid SMPS

Battery  
Charger  
Low Voltage  
High Current

1

60 – 70%

Hybrid SMPS

PA  
Driver  
High Power

4

10 – 20%

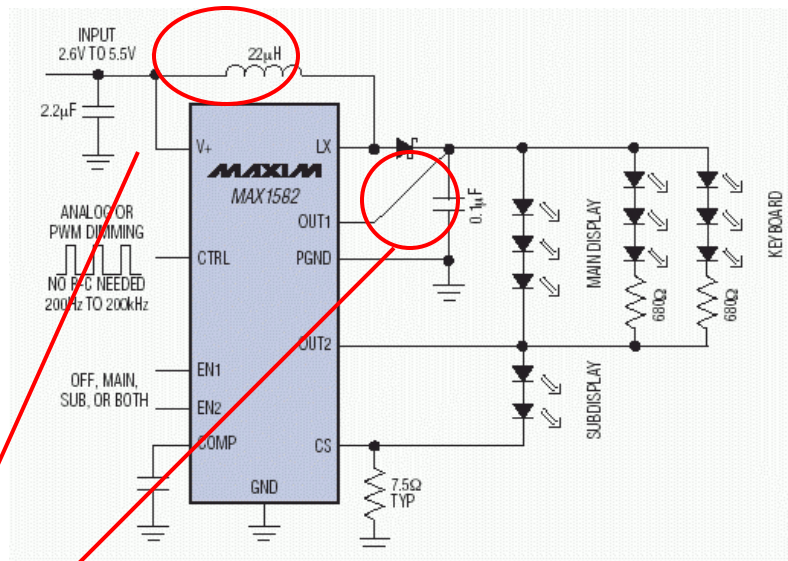
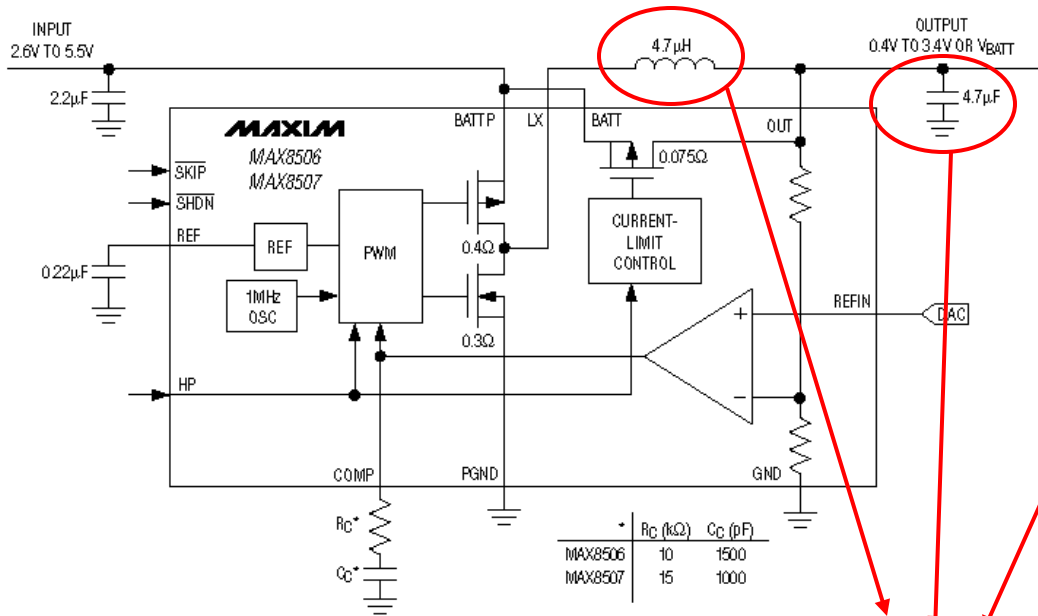
Integrated LDO, SC, CP

Baseband  
(DSP, Arm, Audio  
amp, ...)  
High Speed

# Point-of-Load (POL) Converter Integration

**Maxim 8506-8508 in a Cell Phone PA Power Supply**

**Maxim 1582 in a Notebook White LED Power Supply**



**Large External Passives**

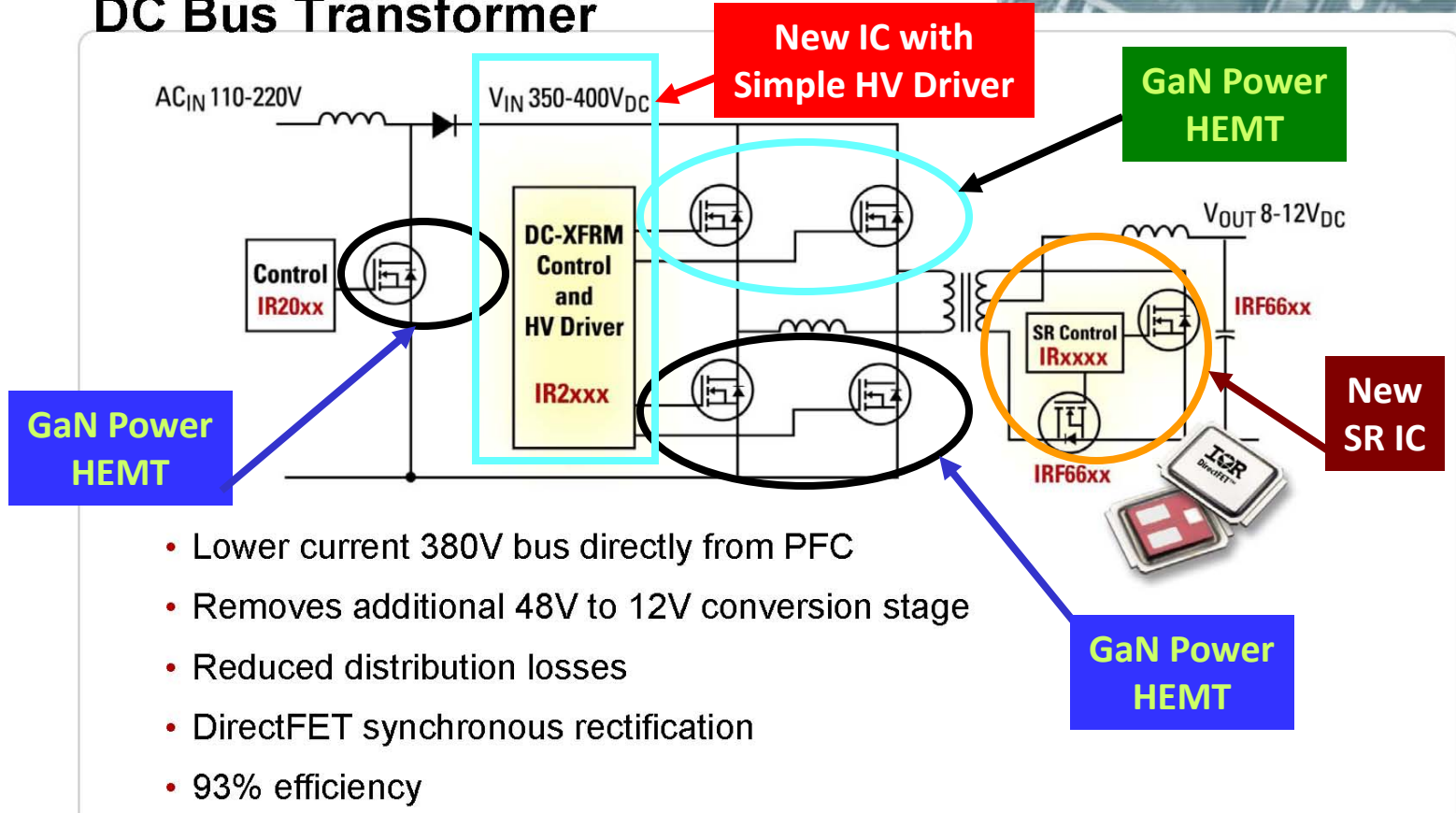
**High-frequency (@ > 1 MHz) switch-mode power conversion facilitates on-chip integration of passive elements.**



# More Integrated Solution in High-End Computer Servers

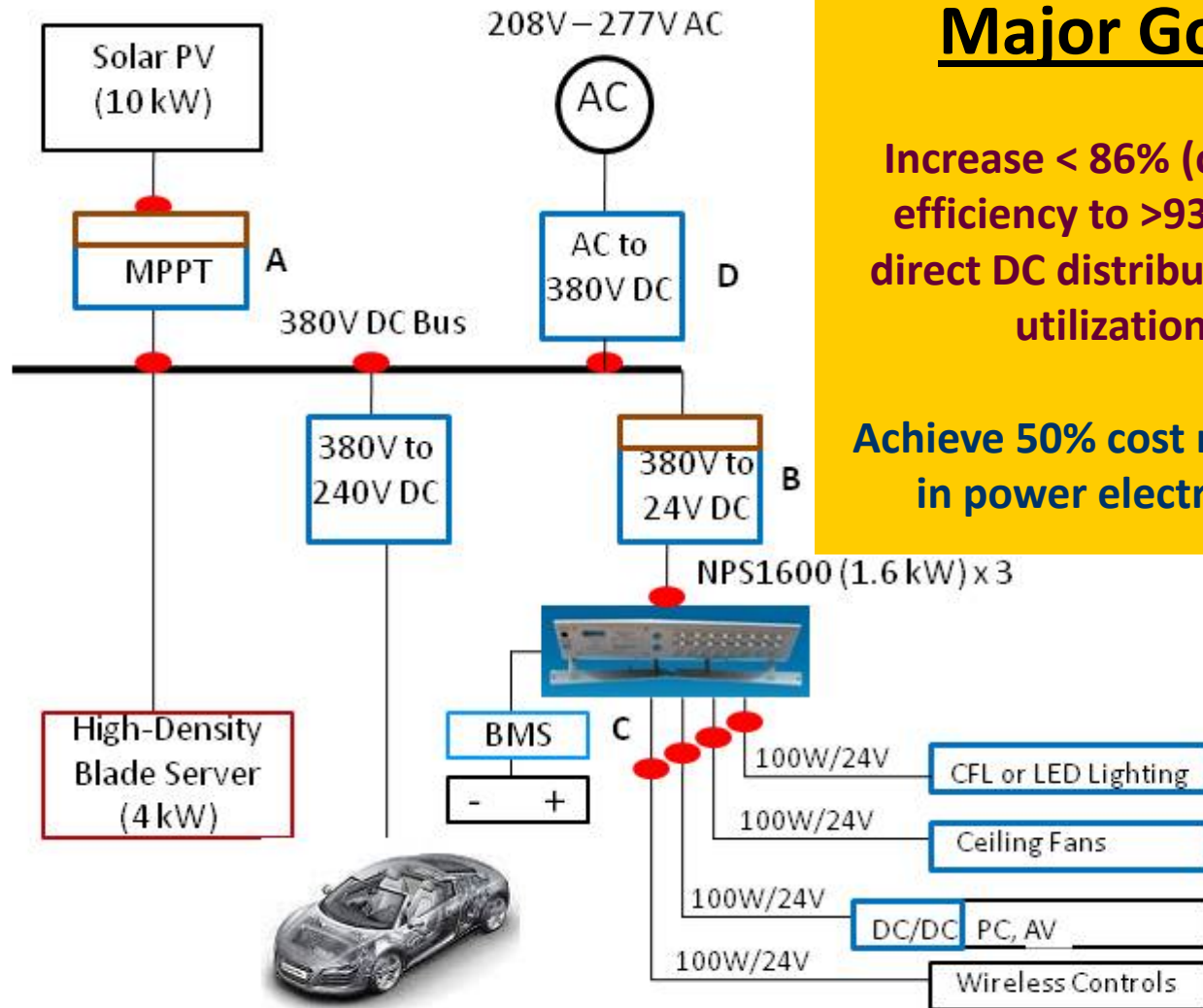
## New Architecture: DC Bus Transformer

POWERING THE DIGITAL FUTURE



**Replace with Efficient Power Switches and IC, Eliminate HV Driver**  
**Increase Overall Efficiency to 93%, Reduce Cost by 60%**

# 10 kW Distributed Smart DC Solar Microgrid



## Major Goal:

Increase < 86% (current) efficiency to >93% with direct DC distribution and utilization.

Achieve 50% cost reduction in power electronics.

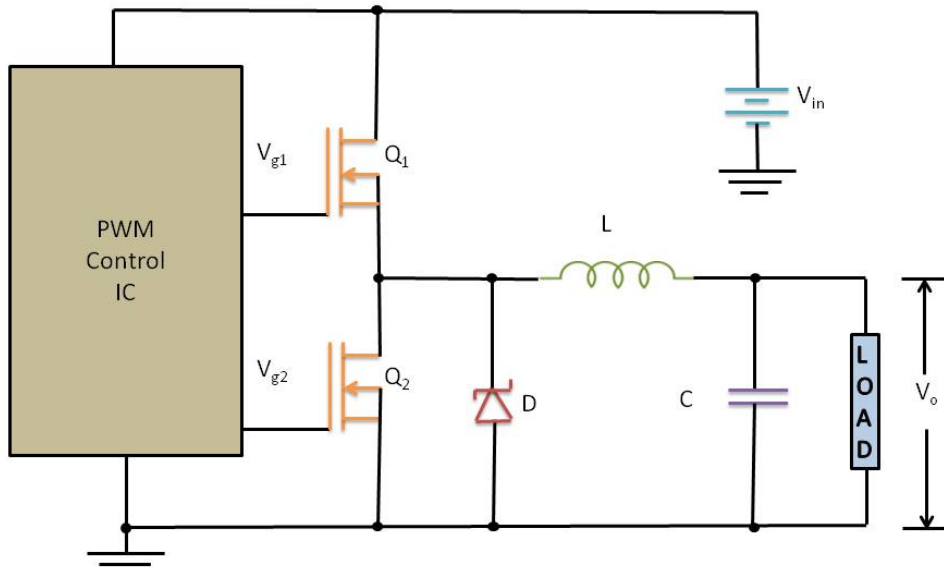
- Monitoring Point
- Nextek Power Systems
- University of Toledo

- A: Maximum Power Point Tracker (MPPT)
- B: 380V/24V DC/DC Converter
- C: Battery Management System
- D: 10 kW AC/DC Rectifier

24V DC is distributed via  
Emerge™ Alliance  
DC Flex Zone Ceiling grid

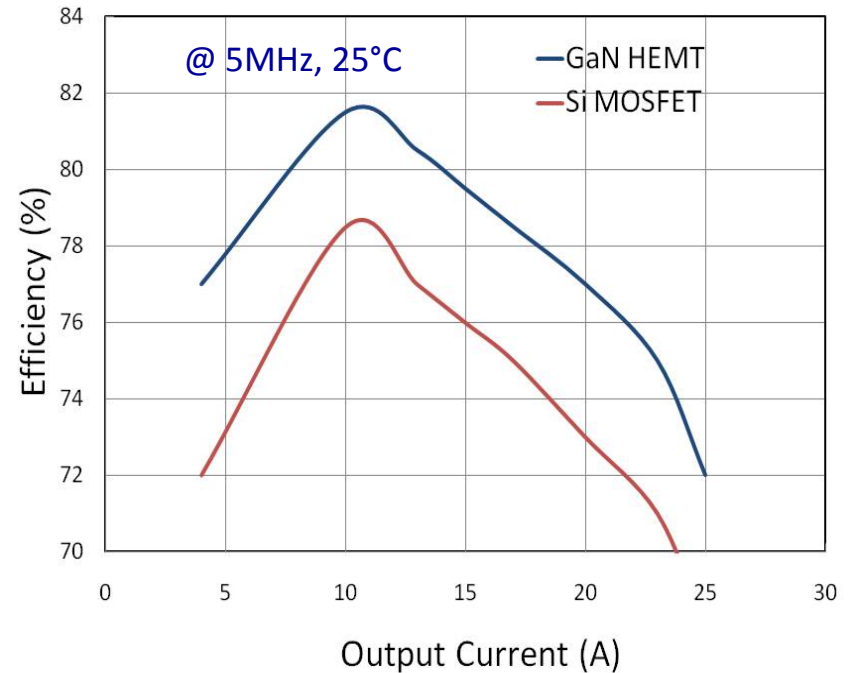


# High-Efficiency Point-of-Load (POL) DC-DC Converter

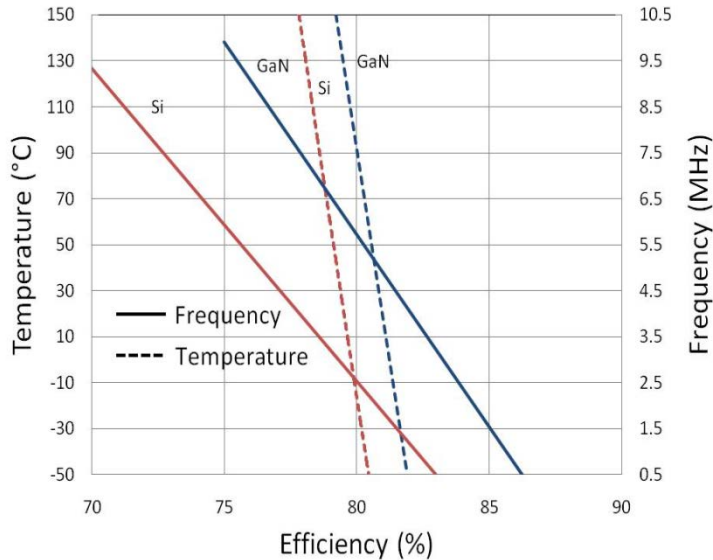


12V/1V, 10W Synchronous Buck Converter

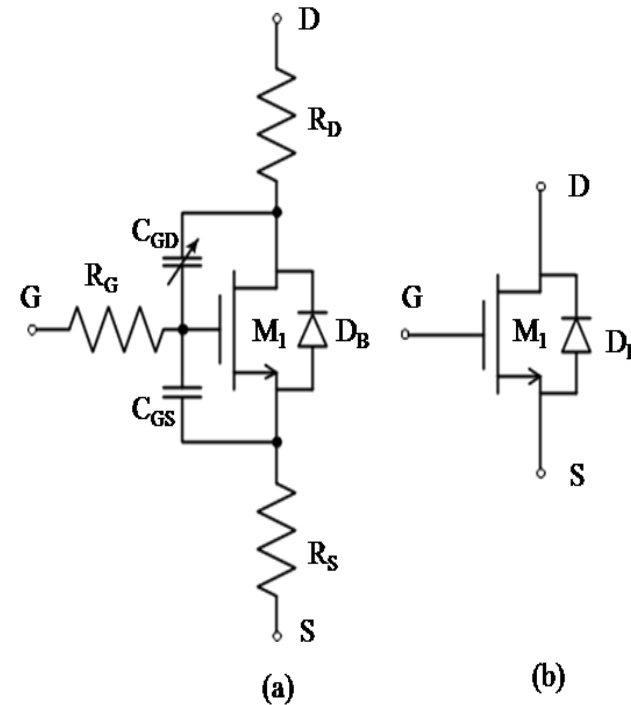
Device	$V_{BR}$ (V)	$V_T$ (V)	$R_{DS(on)}$ (m $\Omega$ )	$C_{ISS}$ (nF)	$C_{OSS}$ (nF)	$C_{RSS}$ (pF)	$Q_G$ (nC)
Best Silicon MOSFET	30	1.6	6	2.3	2	300	40
Best GaN E-Mode HEMT	40	1.4	16	0.3	0.32	50	3



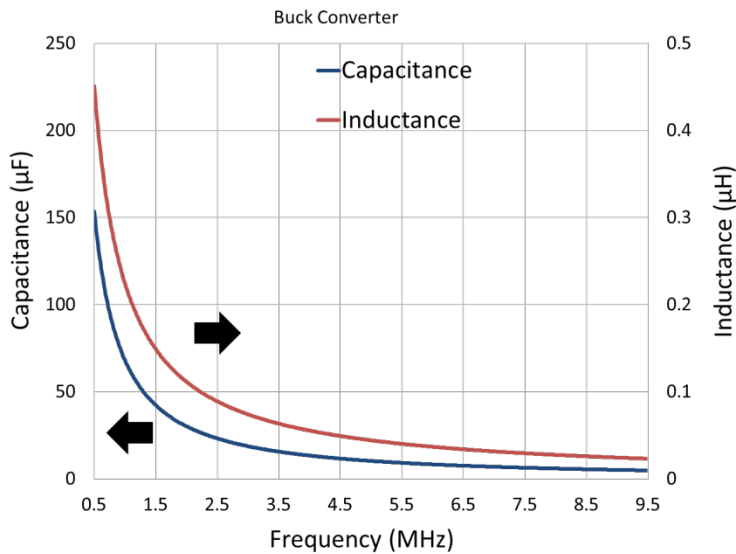
# 12V/1V, 10W Point-of-Load (POL) DC-DC Converter



## Circuit Simulation Model

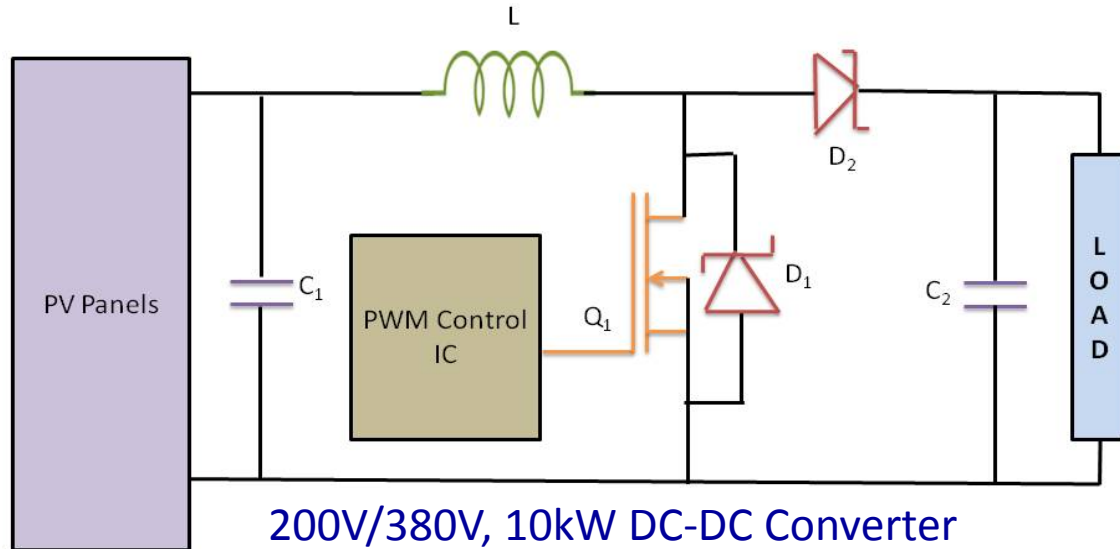


vs. Frequency @ 25°C; vs. Temperature @ 5MHz

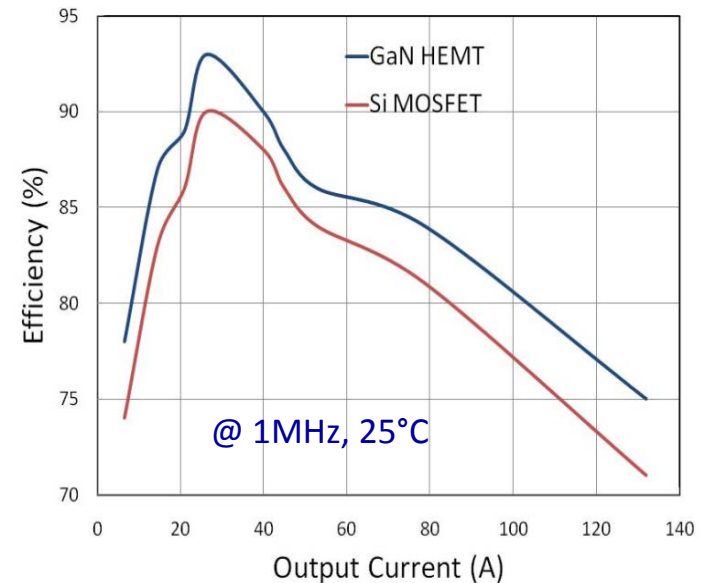


K. Shenai, *IEEE Trans. Power Electronics*, vol. 6, no. 3, pp. 539-547, July 1991.

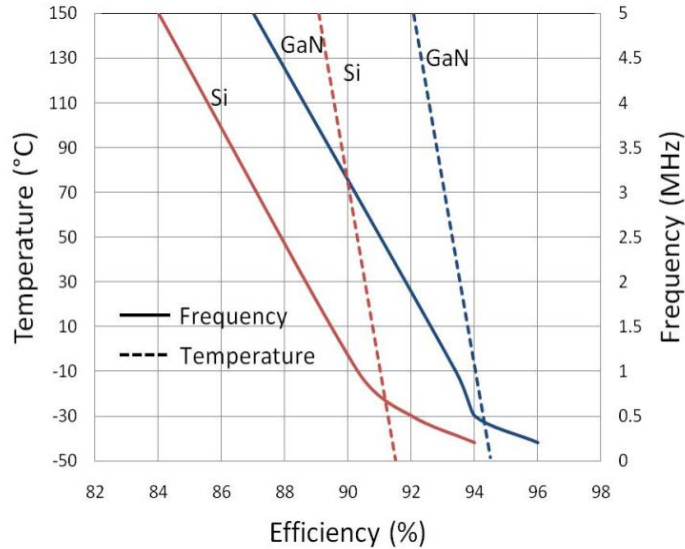
# High-Efficiency Boost Converter



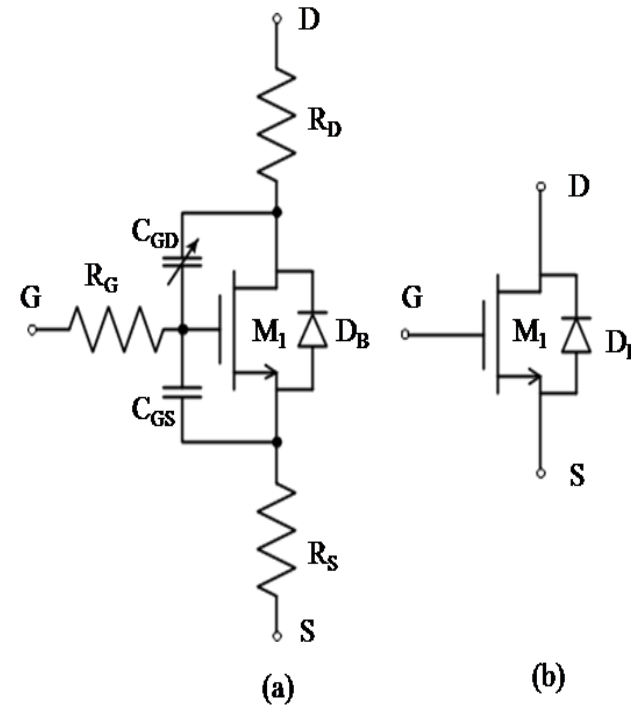
Device	$V_{BR}$ (V)	$V_T$ (V)	$R_{ON}$ (m $\Omega$ )	$C_{ISS}$ (nF)	$C_{OSS}$ (nF)	$C_{RSS}$ (nF)	$Q_G$ (nC)
Best Commercial Silicon MOSFET	600	3	99	4.5	20	1.8	60
Scaled GaN E-Mode FET	600	1.4	40	1.5	2.1	0.3	45



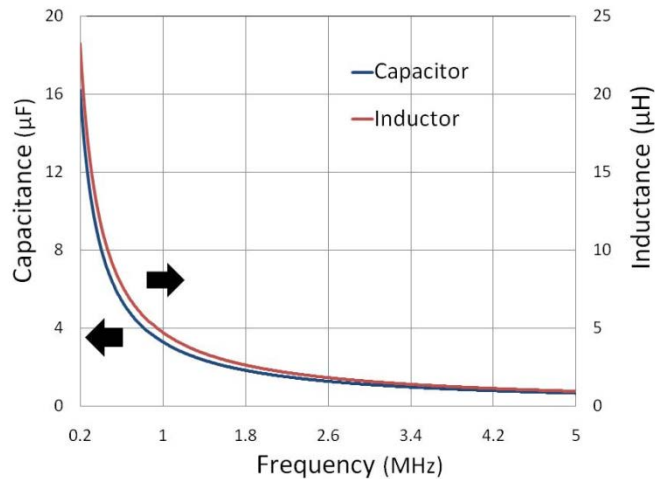
# 200V/380V, 10kW DC-DC Converter



## Circuit Simulation Model



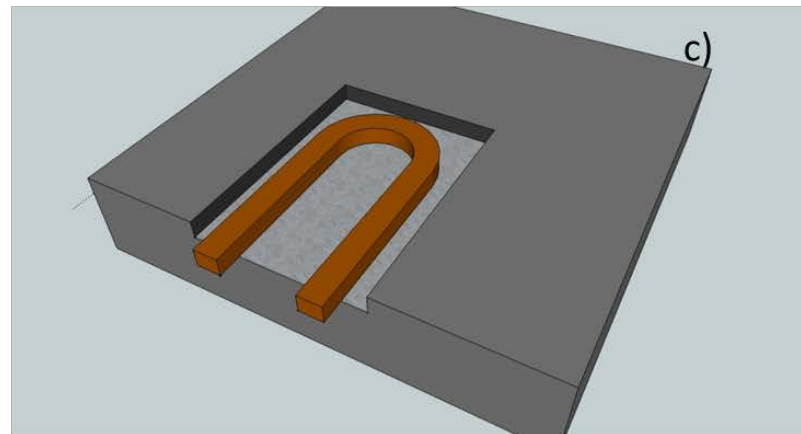
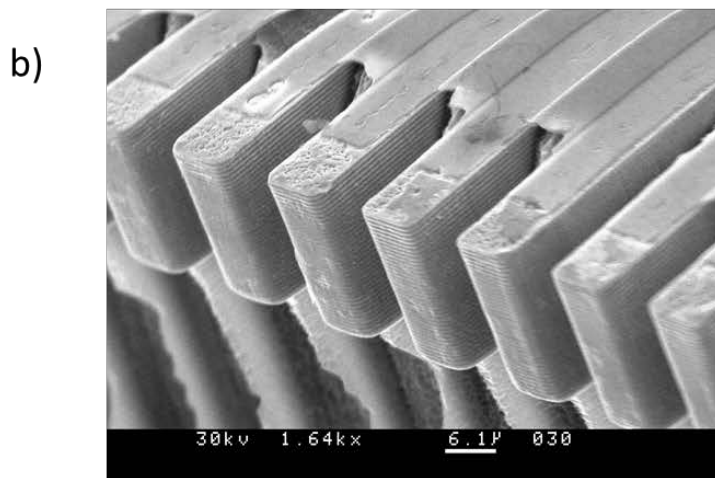
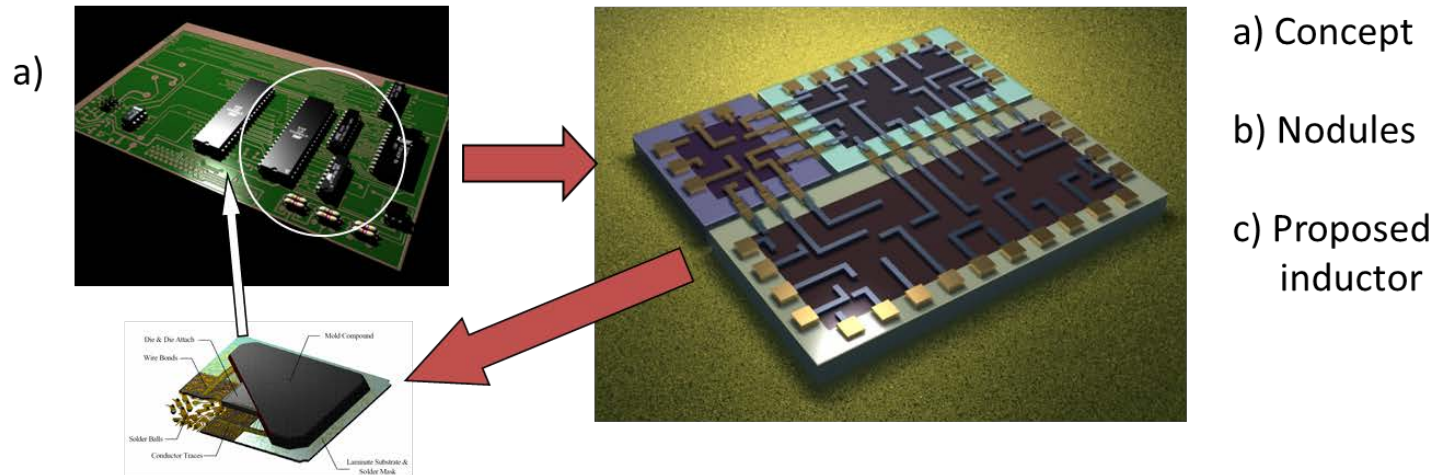
vs. Frequency @ 25°C; vs. Temperature @ 1MHz



K. Shenai, *IEEE Trans. Power Electronics*, vol. 6, no. 3, pp. 539-547, July 1991.

# Chip-Scale Power Integration

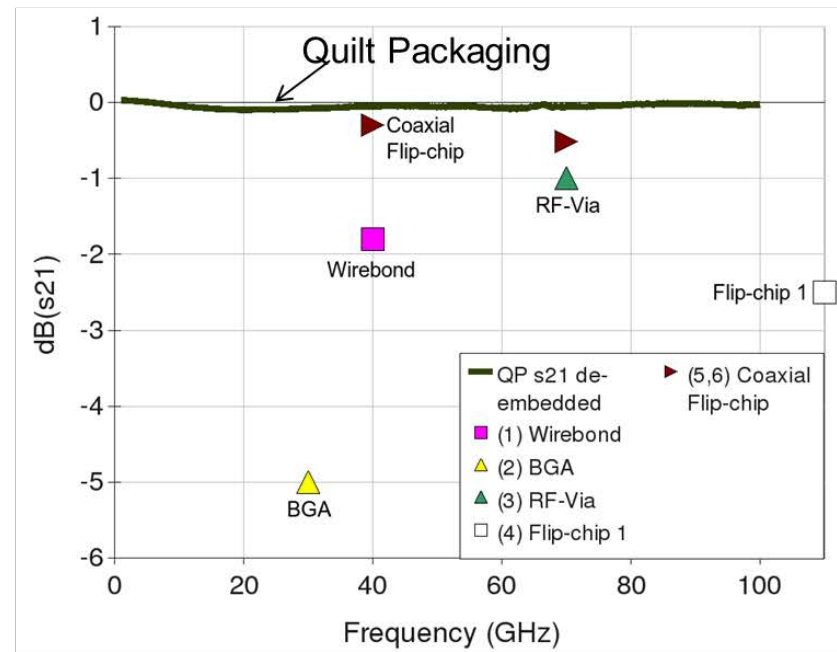
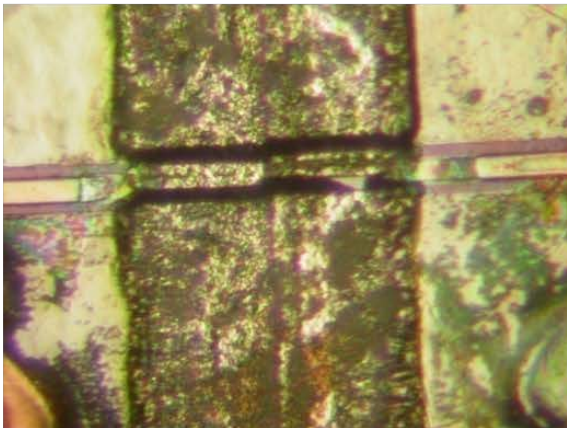
## Notre Dame “Quilt Packaging”



# Chip-Scale Power Integration

## QP Allows World-Record Chip-to-Chip Bandwidth

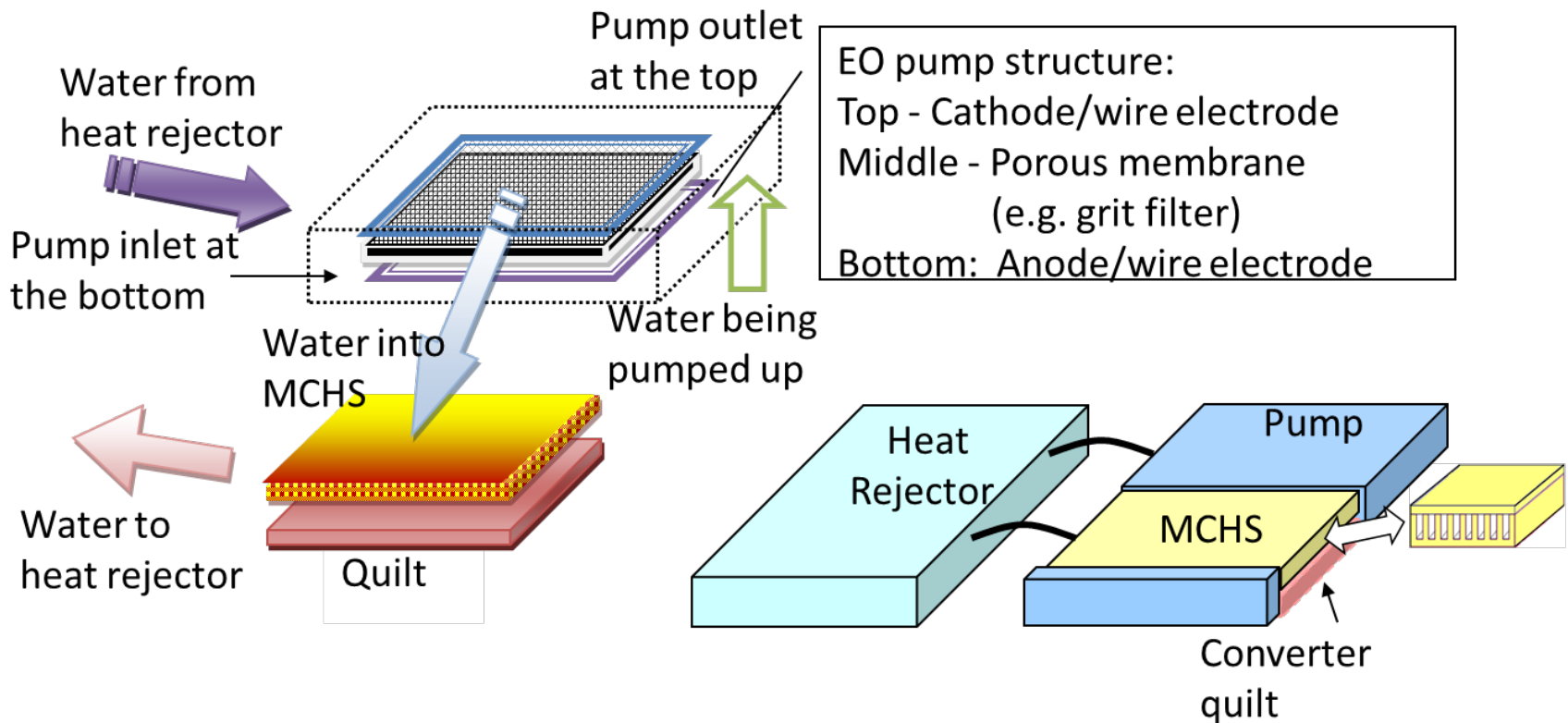
- De-embedded insertion loss compared with recent papers on wire bonds, ball grid array, MS-to-CPW RF-via, flip chip.
- 0.25 dB lower than coaxial flip-chip via at 40 GHz
- 1.7 dB lower than standard flip-chip at 110 GHz
- 0.8 dB lower than RF-via at 70 GHz



**Collaborator:** Dr. Gary H. Bernstein (University of Notre Dame)

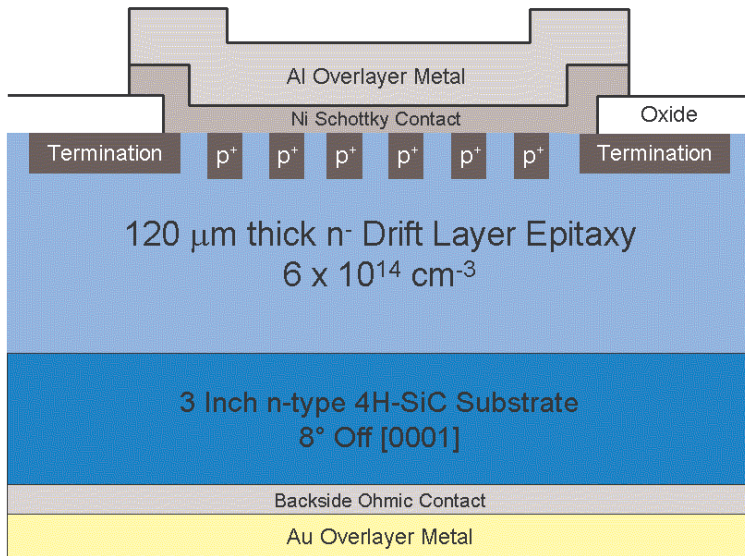
# Power Chip Cooling

## Electro Osmotic DC Micro Cooling



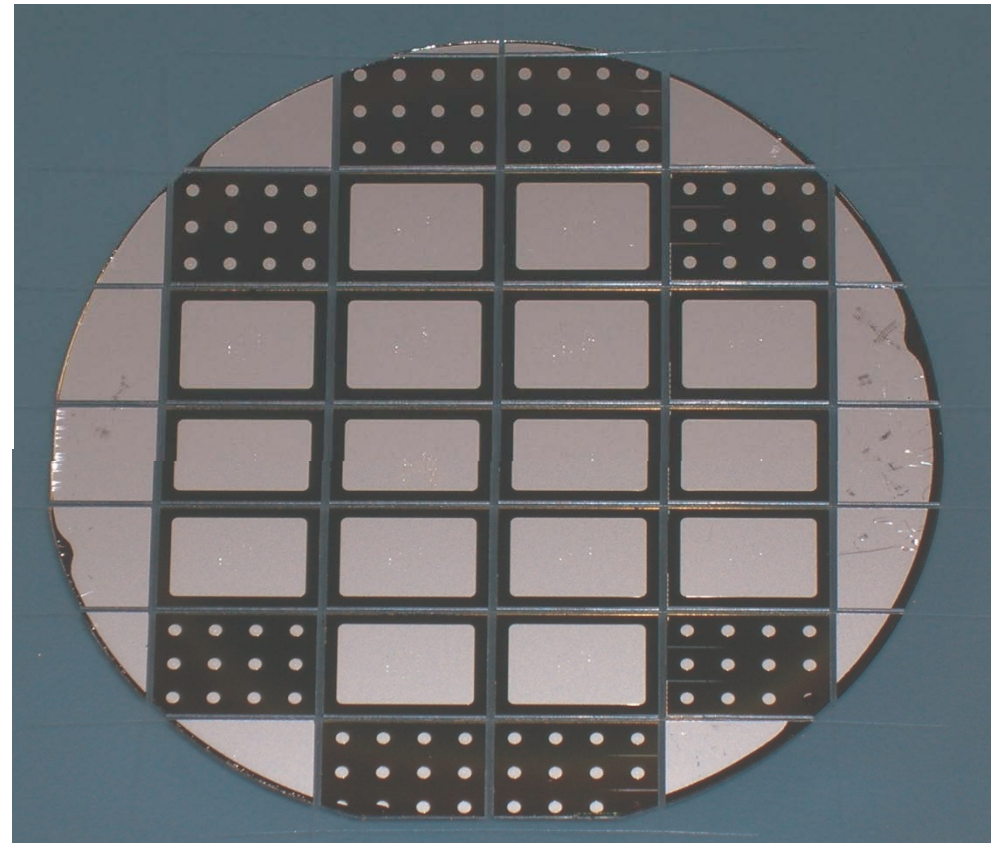
**Collaborator:** Dr. Jayne Wu (University of Tennessee at Knoxville)

# Current Status of Best R&D SiC JBS Rectifier



**Cross section of 10 kV SiC JBS rectifier**  
– **Not commercially available**

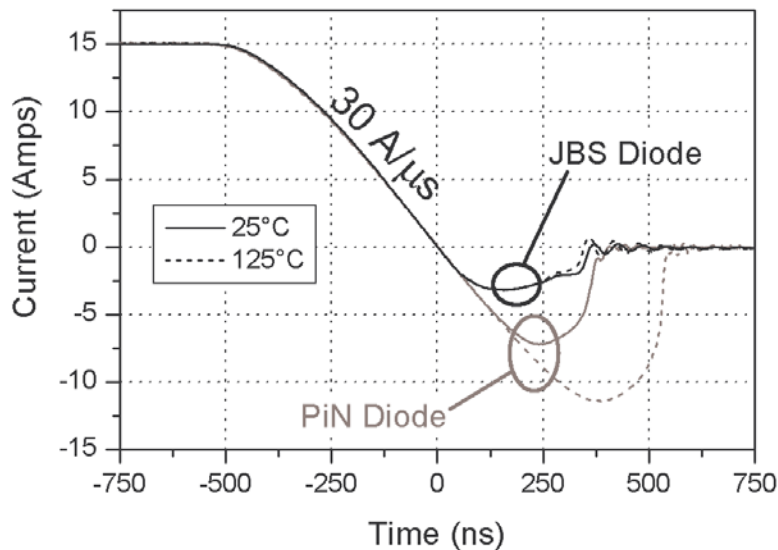
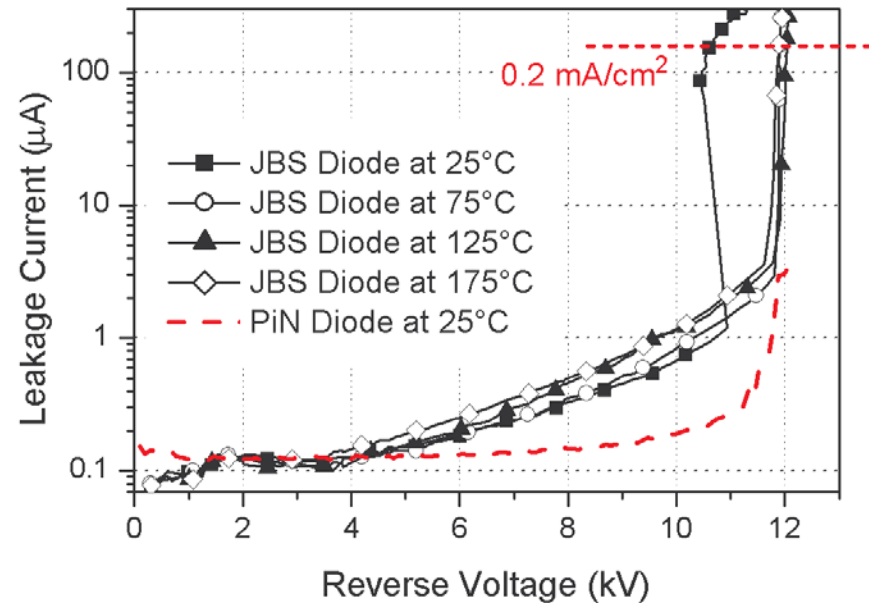
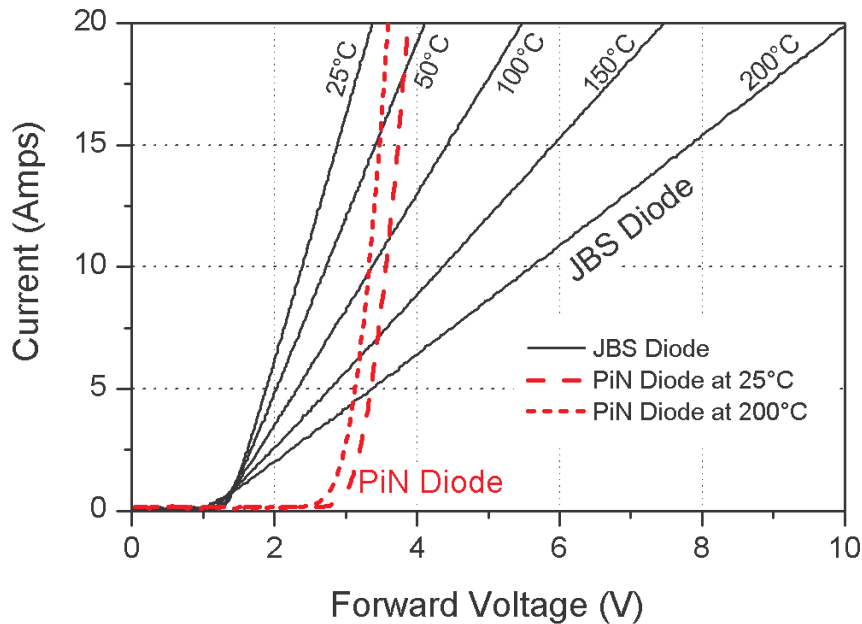
**Device fabricated on best R&D 3 inch SiC PVT wafers with nearly zero micro pipes and lowest screw dislocation density**



**10 kV/20A SiC JBS rectifier on 3 inch wafers–**  
**Not commercially available**

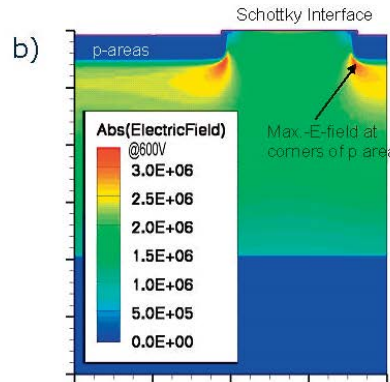
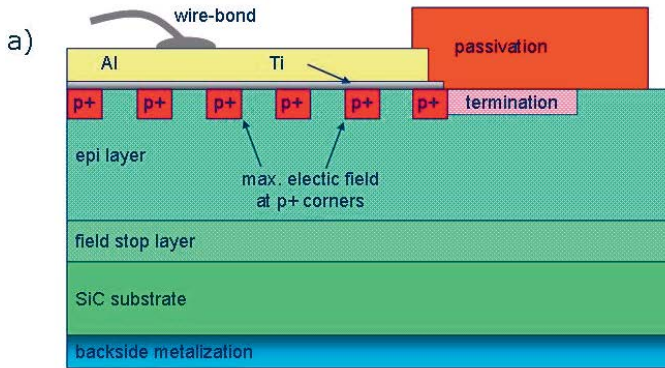


# Current Status of Best R&D SiC JBS Rectifier



**Breakdown voltage derated by 40%**  
**Majority carrier diode**  
**High leakage current**  
**Nothing reported on reliability**

# Current Status of Best Commercial SiC MPS Rectifier



**1.2 kV/20A diode**

**Breakdown voltage derated by 30%**

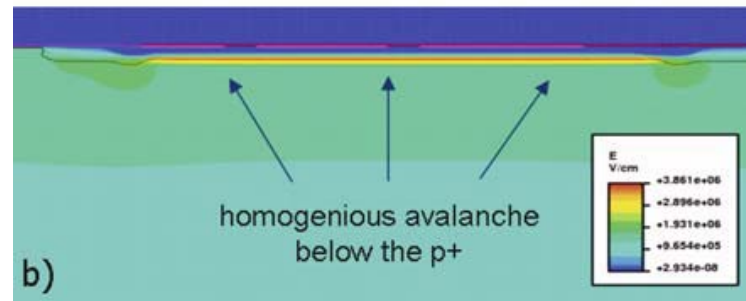
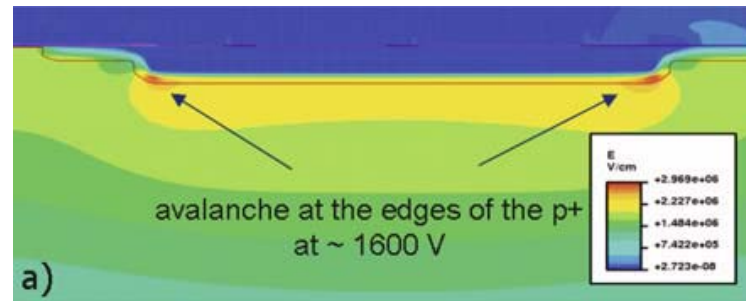
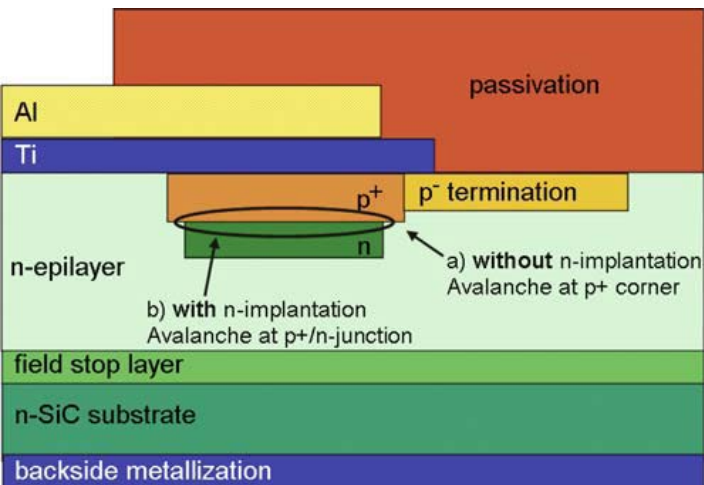
**Breakdown at edge termination**

**Majority carrier diode**

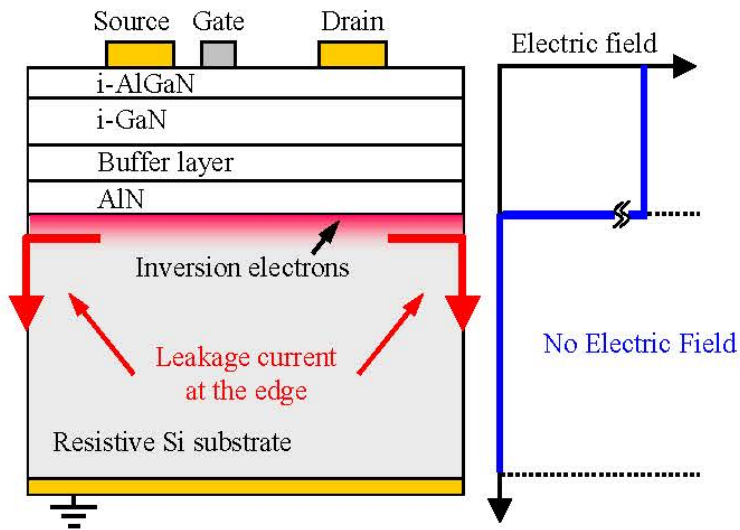
**High leakage current**

**Poor  $dv/dt < 50V/ns$**

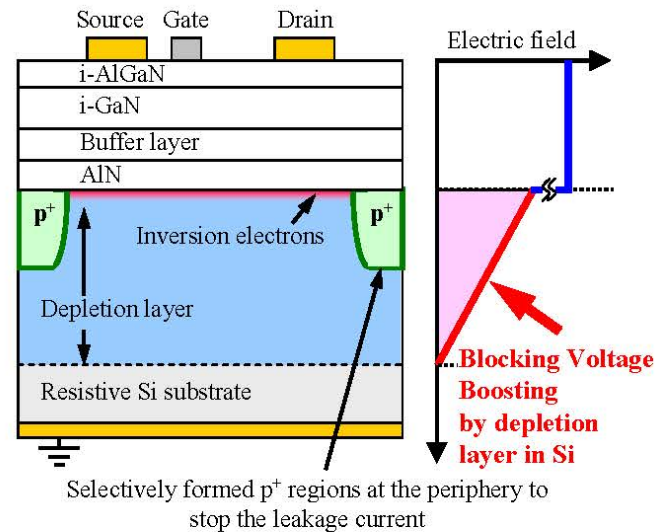
**Nothing on switching reliability**



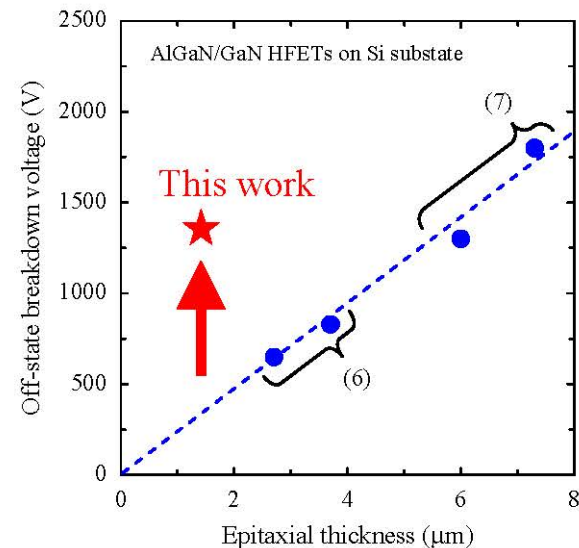
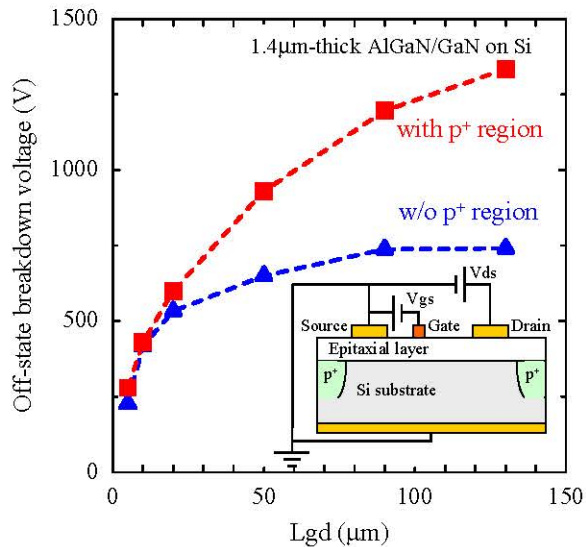
# High-Voltage GaN HFETs



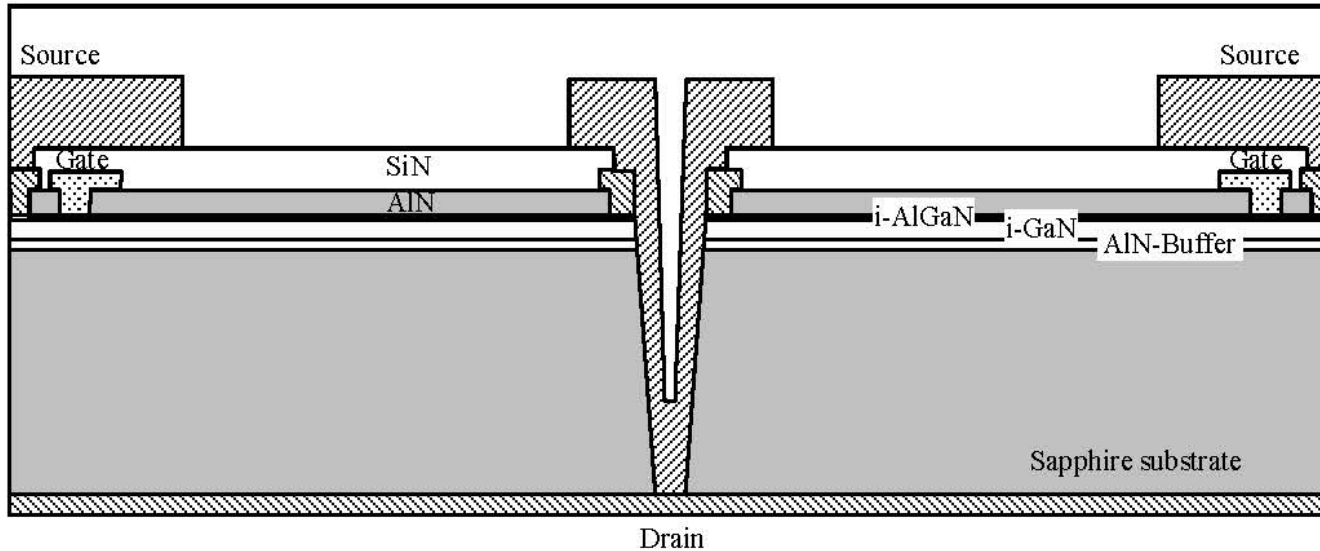
(a) Conventional HFET



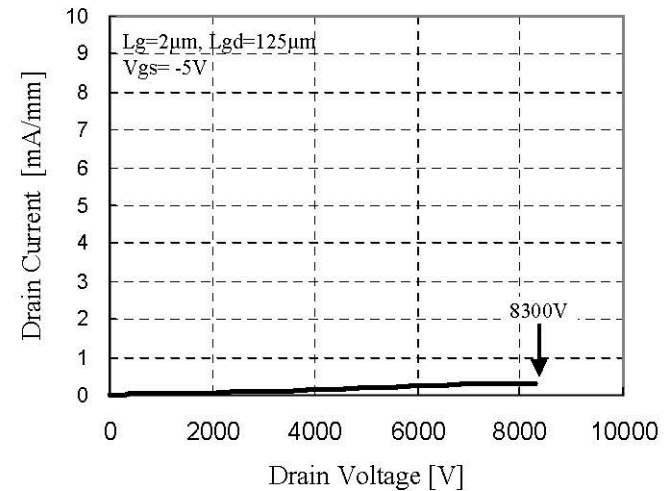
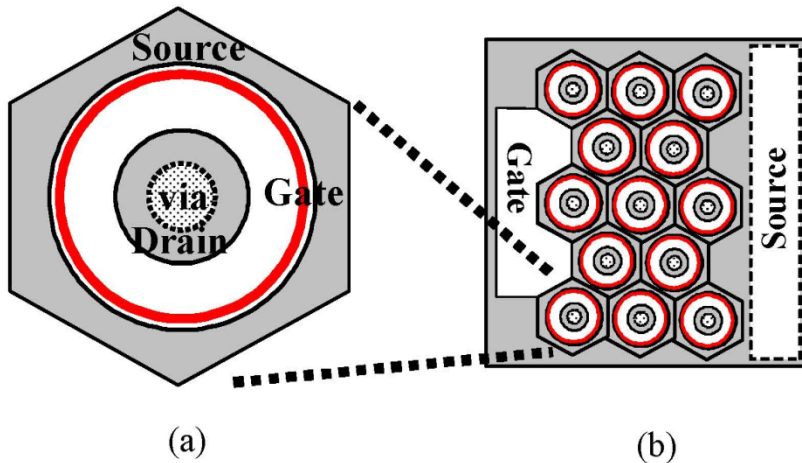
(b) Proposed HFET with channel stoppers



# High-Voltage GaN HFETs



8300V,  $R_{sp} = 186 \text{ m}\Omega \times \text{cm}^2$



# Current Status

## Best Commercial SiC Devices:

1700V/25A Schottky Barrier Diode

1200V/33A MOSFET

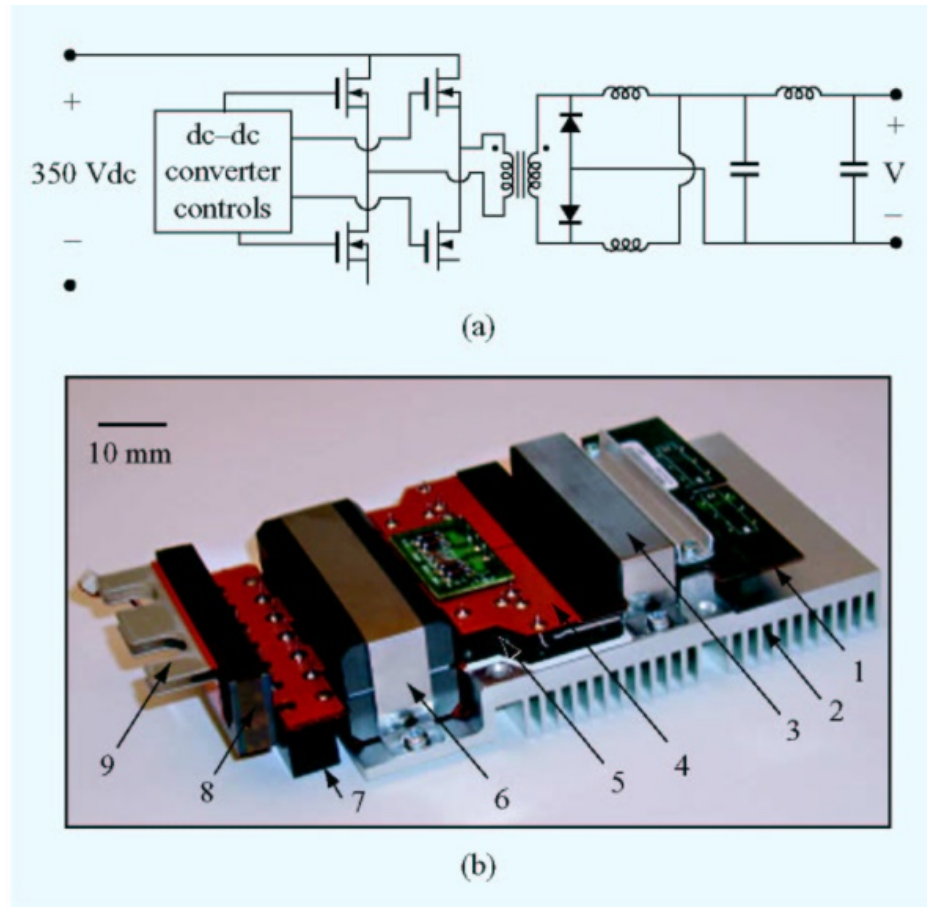
## No Commercial GaN Power FETs

Too Expensive  
Reliability Unknown

# **Power Semiconductor Switch Reliability**

**Lessons Learned from Silicon  
Power MOSFET Failures in  
High-Density Power Supply  
Field-Reliability Study**

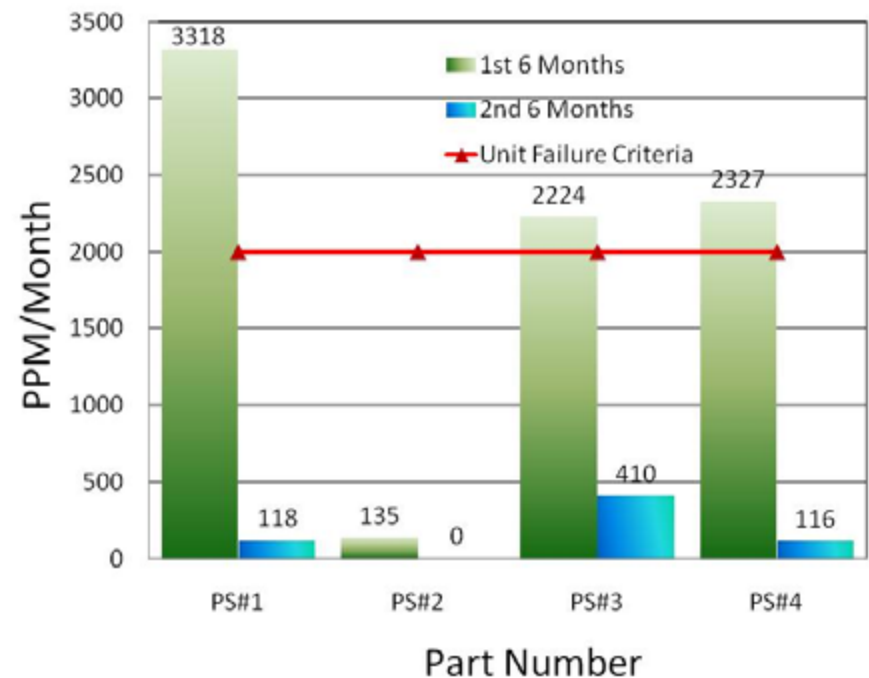
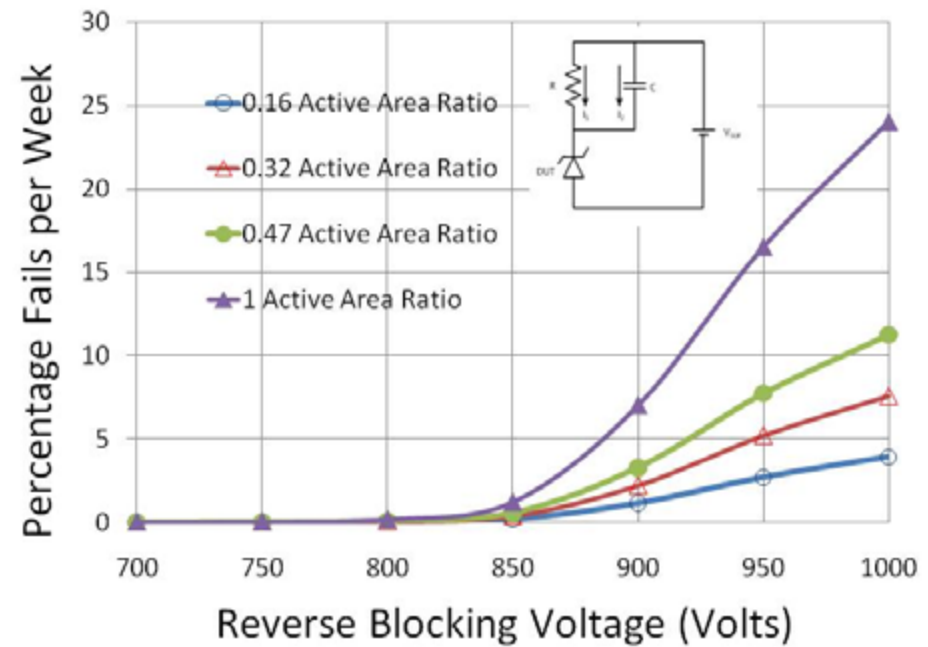
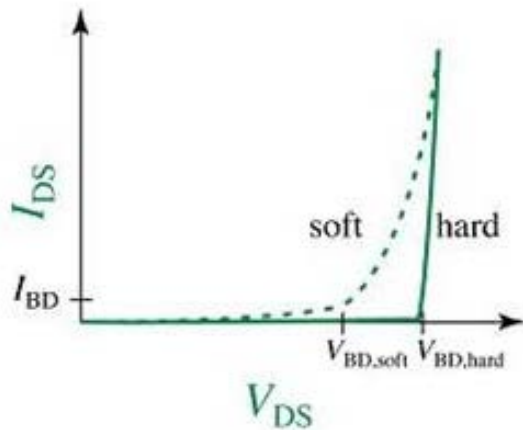
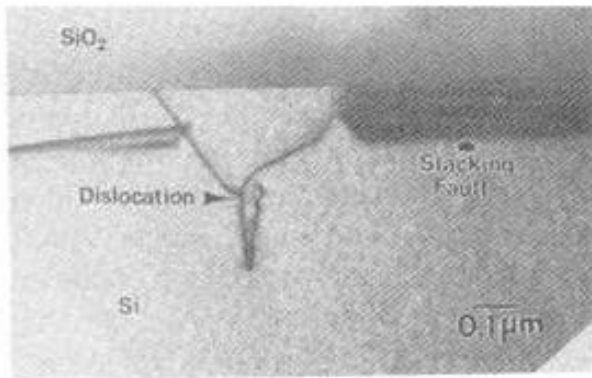
# Power Supply Reliability Study



**Field-reliability of computer/telecom power supplies was extensively evaluated to study the cause of power MOSFET failures.**

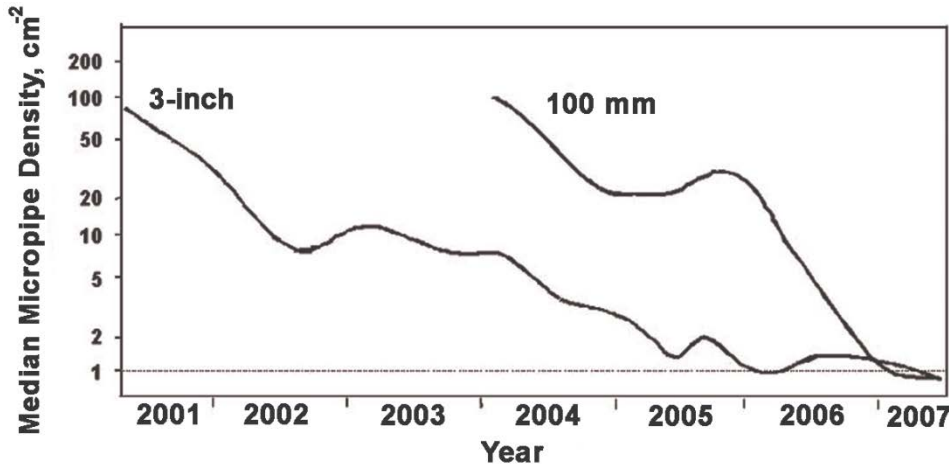
*K. Shenai, IEEE NAECON 2010, Dayton, OH, July 2010*

# Material Defects Caused Field- Failures of Silicon Power MOSFETs

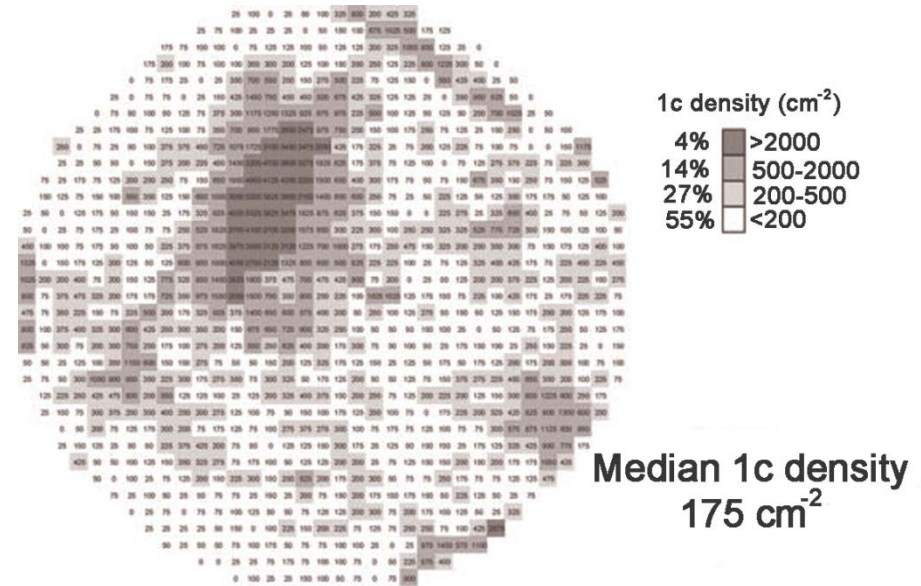




# Current Status of Defect Density in Best R&D SiC Wafers



Nearly Zero (0.8 cm<sup>-2</sup>) Micropipe Density in  
4 inch Commercial SiC PVT Wafers - **Expensive**



Best Screw Dislocation Density in  
3 inch R&D SiC PVT Wafers – **Very Expensive**

Leonard et al, *Mat. Res. Forum*, vols. 600-603, pp. 7-10, 2009 - Cree paper

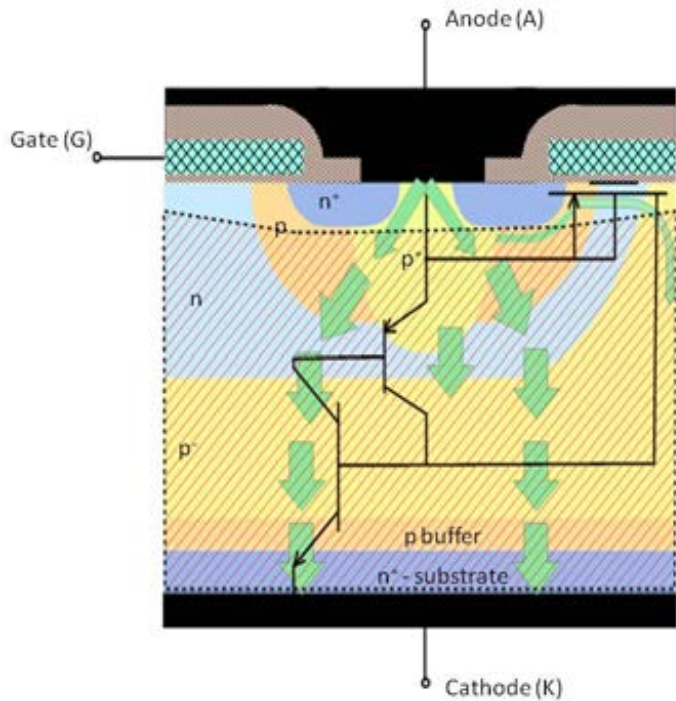
The best R&D SiC PVT wafers have a wide range of defect density  
from < 200 cm<sup>-2</sup> to more than 2,000 cm<sup>-2</sup>

Carrier lifetime control is nearly impossible

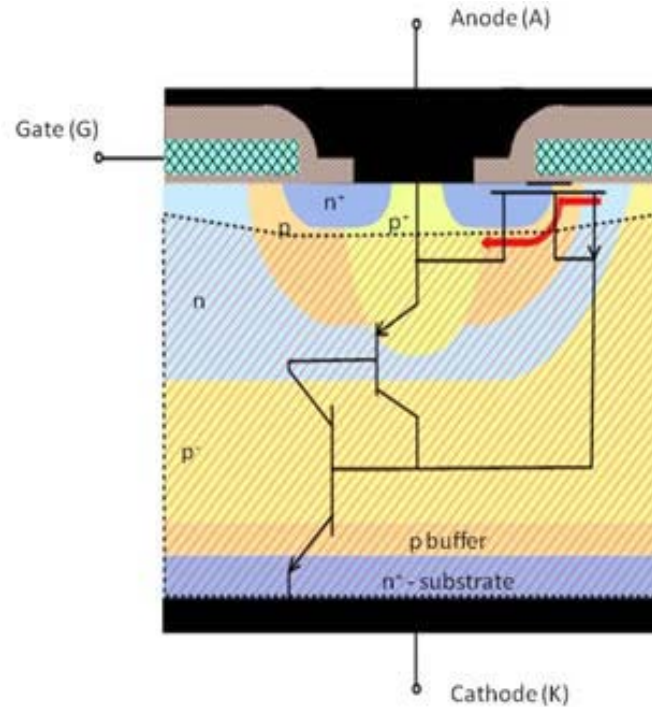
# The Key Question:

If silicon (with  $< 10$  defects/cm<sup>2</sup>) power MOSFET reliability is compromised by material defects, what is the reliability of power switching devices made on SiC (with  $> 10^3$  defects/cm<sup>2</sup>) or GaN (with  $\sim 10^7$  defects/cm<sup>2</sup>) ?

# Turn-off Failures of Silicon MOS-Controlled Thyristors (MCTs)



➔ Current Flow  
▨ Electron-Hole Plasma



➔ Electron Flow  
▨ Electron-Hole Plasma

Plasma Constriction  
Current Filamentation

# Summary & Conclusion

**To:**

**Reduce Cost & Develop Reliable Power Switch in SiC and GaN Semiconductors**

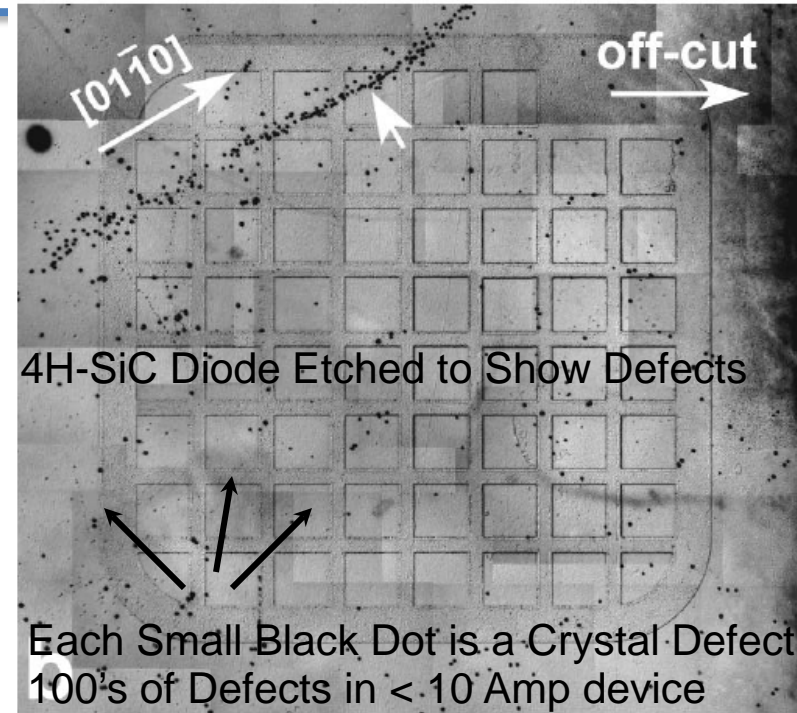


**Material Defects & Structural Limitations  
Must be Eliminated**

# “Game Changing” Technology

Best 0.2 x 0.2 mm SD-free 3C mesa  
(oxidized to map polytype and defects)

Defect-free SiC  
Need Further R&D



0.3 mm

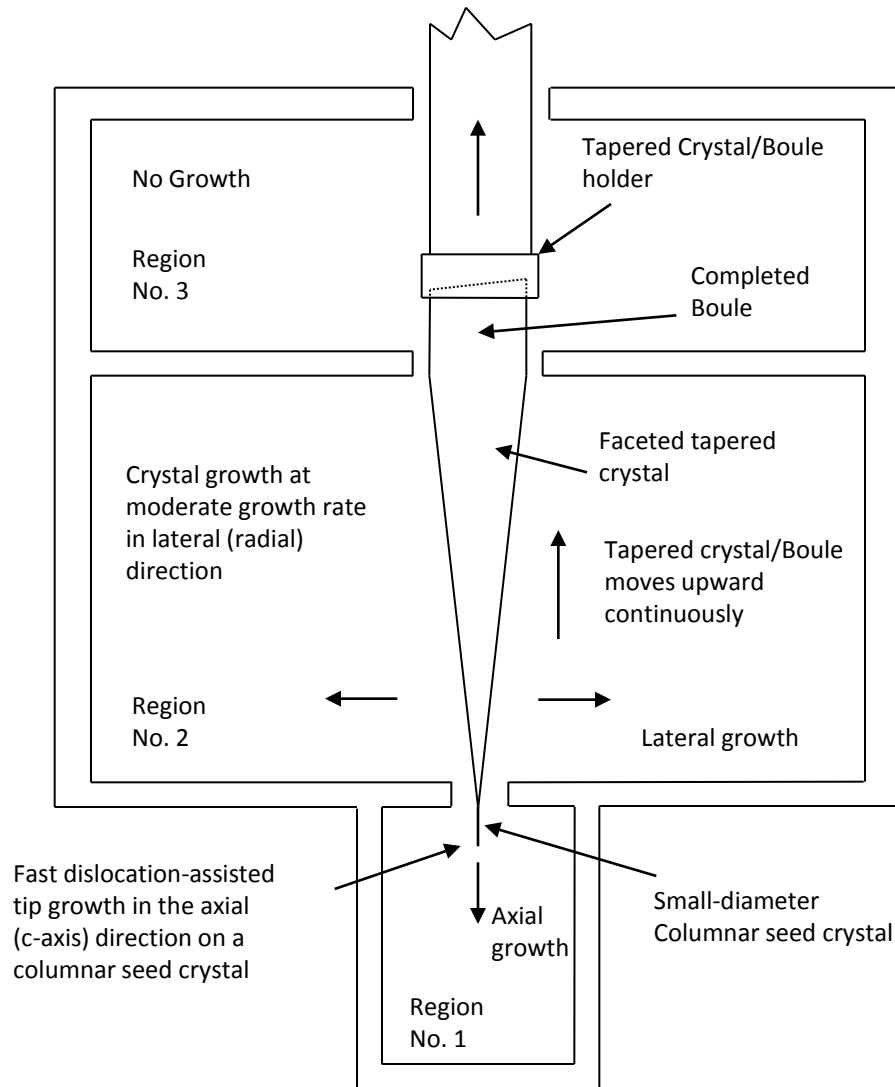
- 4 in. dia. low-cost, low defect-density commercial wafers
  - Robust high-performance devices
  - Low-cost manufacturing
  - 250C packaging and 300C sensors



# LTC Game Changing Technology

Large Tapered Crystal (LTC) Growth Method for SiC (US Patent # 7,449,065B1)

Simplified Schematic Cross-Sectional Representation



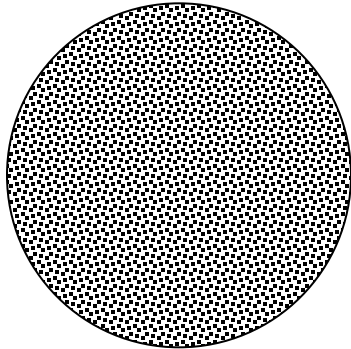
## Features (one embodiment):

1. 3-Region growth apparatus for 3 different growth actions.
2. Region 1: Axial (c-axis) growth on a very small diameter columnar portion enables fast growth in the c-axis direction.
3. Region 2: Lateral (m-direction) growth at moderate growth rate on the tapered portion
4. Region 3: No growth after LTC boule reaches desired diameter.
5. Growth rate of boule in c-axis direction equals fast growth rate of columnar seed crystal.
6. Boule contains only one SD along its axis; the remainder of the boule is nominally defect-free.

# LTC Game Changing Technology

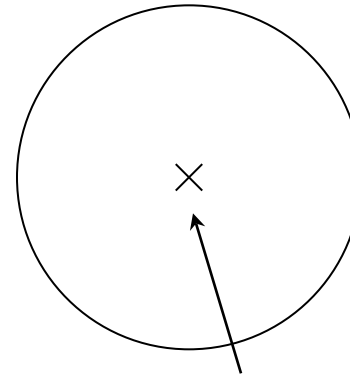
LTC Vision: Dramatically improved SiC wafer quality realized at higher volumes and lower production cost.

**Present-Day SiC Wafer**



~100-10,000 screw dislocations/cm<sup>2</sup>  
< 0.5 wafers per hour  
Cost: > \$2,000/4-inch wafer  
Commercial Power Devices  
Limited to < 50 A, ~1 kV

**LTC SiC Wafer**



< 1 screw dislocation/cm<sup>2</sup>  
> 1 wafer per hour  
Cost: < \$500 /6-inch wafer  
Commercial Power Devices  
100-1000 A, > 10kV

**Drastic wafer improvement sufficient to unlock full SiC power device potential.  
(Approach also applicable to 3C-SiC, GaN, Diamond, and other semiconductors)**

Collaborators: Mike Dudley (SUNY - SB)  
Phil Neudeck, Andy Trunek, and A. Powell (NASA – GRC)

**We can do it !**



**Any Questions ?**